

Erratum: "Ultraviolet poling of pure fused silica by high-intensity femtosecond radiation" [Appl. Phys. Lett. 86, 071106 (2005)]

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In our paper, Eqs. (1) and (2) were typed erroneously. In order to get the correct form, they should be decreased by a factor of 2 on their right hand sides. The equations should read as follows:

$$I = \frac{\varepsilon_p}{\left(\frac{\pi}{\ln 2}\right)^{3/2} \frac{\pi w^2}{2} \left(\frac{F-S}{F}\right)^2}, \quad (1)$$

$$E = \frac{\varepsilon_p N}{\frac{\pi w^2}{\ln 2} \left(\frac{F-S}{F}\right)^2}. \quad (2)$$

In addition, the w parameter used in these equations is not the beam diameter, as written in the text; it is the beam radius and should be twice less, $w=0.15$ cm.

These errors occurred in the rearranging of the original formulas dealing with Gaussian parameters of the beam (at the e^{-1} level), used in the processing of the experiment, to formulas using FWHM parameters. Hence, these errors do not affect any result presented in this letter.